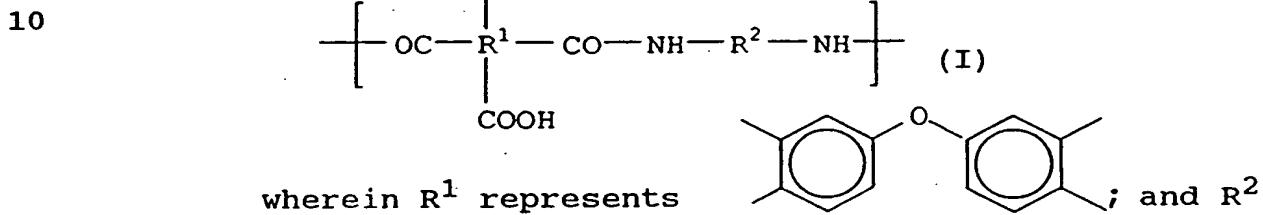


**Abstract:**

There are disclosed a photosensitive resin composition which comprises

5 (A) a polyamic acid having recurring units represented by the formula (I):



15 represents a divalent organic group, and

(B) an acryl compound having an amino group, and also a photosensitive resin composition for an

20 i-line stepper which further comprises a photoinitiator in addition to the photosensitive resin composition.